Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1097	screen adj oxide	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/12 06:56
L2	83433	ion adj implantation	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/12 06:56
L3	656	1 and 2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2006/05/12 07:01
L4		10/750021.app.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/12 08:13
S1	45	("4534826" "5308784" "5753549" "6107143" "4571819" "5422295" "5496745" "5789769" "5889335" "5915190" "6121102" "6140208" "6214695" "6218262" "6221733" "6214695" "6218262" "6221733" "6232181" "4576834" "4630356" "4755477" "5290396" "5298110" "5346584" "5360753" "5395790" "5441094" "5447884" "5478760" "5646052" "5747376" "5804490" "5811345" "5856230" "5858857" "5969393" "6069057" "6117740" "6133113" "6146970" "6165899" "6204185" "6225171" "6225187" "6225171" "6225187" "6225171" "6225187" "6245681" "4389294" "4389281").pn.	USPAT	OR	ON	2006/05/12 06:56
S2	2382	dry adj oxidation	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR ·	ON .	2006/04/17 16:42

S 3	1603408	semiconductor	US-PGPUB;	OR	ON	2005/11/08 14:04
		-	USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	·		
S4	1864	S2 and S3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 14:04
S5	139489	oxide adj layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 14:04
S6	52618	nitride adj layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 14:05
S8	585	S4 and S5 and S6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 14:05
S9	109889	trench	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 14:05
S10	300	S8 and S9	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2006/04/17 17:09
S11	9176	isotropic adj etching	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 15:19

S13	2847	S9 and S11	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 15:20
S14	877	S13 and S5 and S6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 15:21
S15	14	S14 and S2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 15:21
S16	3	"4104086".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 16:03
S17	4	(("6444540") or ("6500727") or ("6218309") or ("6579801")).PN.	USPAT	OR	OFF	2006/04/17 17:40
S18	9671	hydrogen adj bromide and chlorine	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/17 17:41
S19	116401	trench	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2006/04/17 17:58
S20	2499	dry adj oxidation	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/17 17:41
S21		S18 and S19 and S20	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/17 17:52

S22	104233	nitride adj (layer or liner or film)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2006/04/17 17:56
S23	299272	oxide adj (layer or liner or film)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/17 17:56
S30	2	"4571819".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/17 17:58
S31	89	("4571819").URPN.	USPAT	OR	ON	2006/04/17 17:59
S32	4	S20 and S31	USPAT	OR _.	ON	2006/04/17 17:59
S33	· 1796283	round\$3 or taper\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/11 12:37
S34	42293	hydrogen adj bromide or hbr	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/11 12:37
S35	368302	chlorine or "cl.sub.2"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/11 12:38
S36	4105	S33 and S34 and S35	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON ·	2006/05/11 12:38
S37	154	438/673.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2006/05/11 12:38

S38	908	438/978.ccls.	US-PGPUB; USPAT; USOCR;	OR .	ON	2006/05/11 12:39
			EPO; JPO; DERWENT; IBM_TDB			
S39	297	438/713.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/11 12:39
S40	22	S36 and (S37 or S38 or S39)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/11 13:20
S41	37	"cf.sub.9"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/11 13:41
S42	1004269	oxygen or "o.sub.2"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/11 13:22
S43	31	S41 and S42	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/11 13:42
S44	297	etching near2 native adj oxides	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/11 13:24
S45	297	etching near2 native adj oxide	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/11 13:27

S46	4	removing near4 native adj oxide near4 "cf.sub.4"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2006/05/11 13:27
S47	472	etching near4 native adj oxide	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/11 13:27
S48	0	S43 and S47	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/11 13:40
S49	3	S35 and S43	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/11 13:40
S50	21433	"cf.sub.4"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2006/05/11 13:41
S51	720	S42 and S50 and purge	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/11 13:49
S52	3	(S42 and S50) near4 purge	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/11 13:43
S53	29	(S42 and S50) same purge	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/11 13:43

Page 6 5/12/2006 8:14:28 AM C:\Documents and Settings\qjefferson\My Documents\EAST\Workspaces\10750021.wsp

S54	387	S35 and S51	US-PGPUB; USPAT; • USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/11 13:50
S55	396	(purge or purging) near4 S35	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/11 13:51
S56	. 11	S55 and S42 and S50	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR ,	ON	2006/05/11 13:51

Page 7